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PATENT & TRADEMARK OFFICE

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Entley, William R.; Langan, John G.; Hall, Randy  
Assignee: Novellus Systems, Inc.  
Title: In Situ Plasma Process To Remove Fluorine Residues From The Interior Surfaces Of A CVD Reactor  
Serial No.: 10/003,908 Filing Date: November 1, 2001  
Examiner: Unassigned Group Art Unit: Unassigned  
Docket No.: M-11021 US

San Jose, California  
March 8, 2002

COMMISSIONER FOR PATENTS  
Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT  
UNDER 37 CFR § 1.97(b)

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TC 2800 MAIL ROOM

Dear Sir:

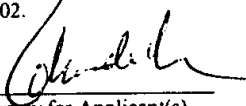
Pursuant to 37 C.F.R. § 1.56, § 1.97 and § 1.98, the documents listed on the accompanying form PTO-1449 are called to the attention of the Examiner for the above patent application. Copies of these documents are enclosed.

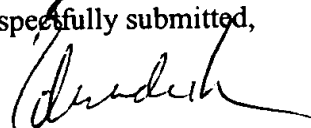
Citation of these documents shall not be construed as:

1. an admission that the documents are necessarily prior art with respect to the instant invention;
2. a representation that a search has been made; or
3. an admission that the information cited herein is, or is considered to be, material to patentability as defined in § 1.56(b).

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I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on March 8, 2002.

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Attorney for Applicant(s) Date of Signature

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